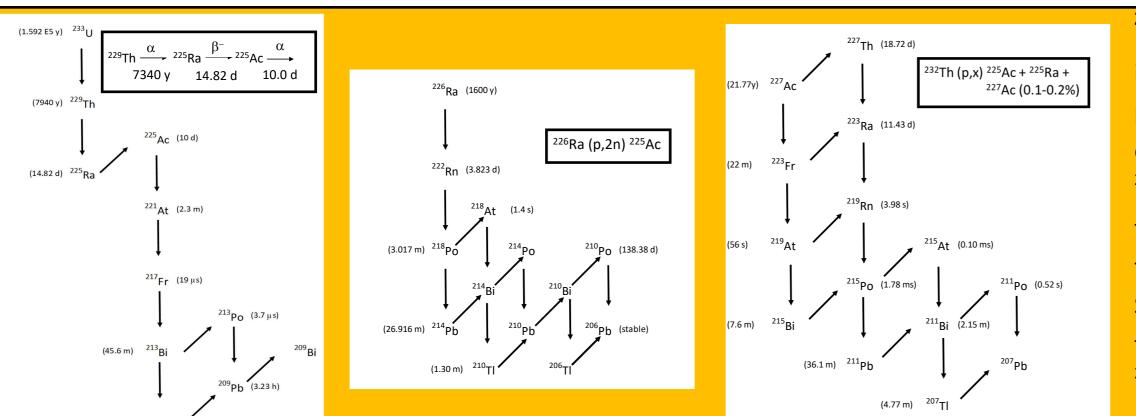
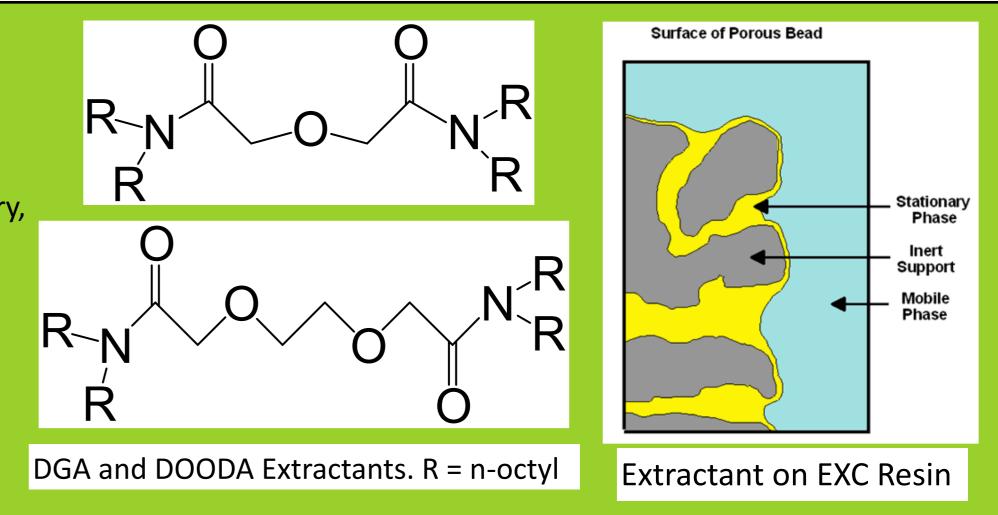
## The Purification of <sup>225</sup>Ac using Extraction Chromatographic Resins Madeleine A. Eddy, Ed Rush, and Daniel R. McAlister Eichrom Technologies, LLC Lisle, IL USA

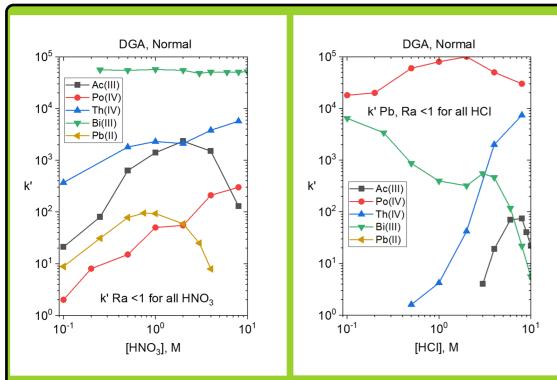
**Abstract:** Extraction chromatographic (EXC) resins consist of hydrophobic extractants physically adsorbed onto porous inert supports. Combining the selectivity of solvent extraction reagents with the ease of use of chromatography, EXC resins have been used extensively in the separation of radionuclides in a number of applications, including bioassay, environmental analysis, geochronometry, and radionuclide production for industry, radiochemistry, and nuclear medicine. EXC resins based on the diglycolamide (DGA) and dioxaoctanediamide (DOODA) extractants show particular promise for the purification of <sup>225</sup>Ac from <sup>229</sup>Th, <sup>232</sup>Th spallation targets, and (p,n) reactions on <sup>226</sup>Ra targets. The DGA and DOODA resins purify <sup>225</sup>Ac from Th, Ra, <sup>226</sup>Ra daughters, <sup>229</sup>Th daughters, <sup>232</sup>Th spallation byproducts, and common reagent impurities. Utilizing both DGA and DOODA resins in combination facilitates the production of highly pure <sup>225</sup>Ac in a matrix compatible with chelator chemistry.

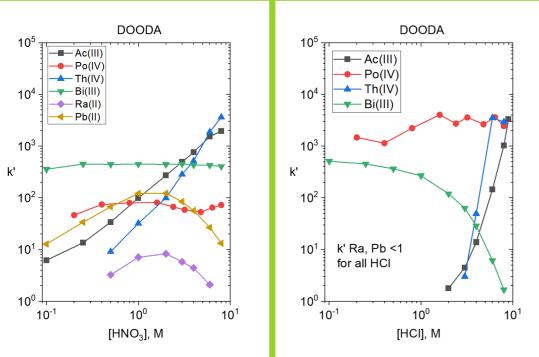




<sup>225</sup>Ac production: There are several possible routes to large-scale production of <sup>225</sup>Ac, including the decay of long-lived <sup>229</sup>Th source material, proton irradiation of <sup>226</sup>Ra targets, and proton spallation on <sup>232</sup>Th targets. Each of these production routes poses unique separation challenges. Separation of <sup>225</sup>Ac and <sup>225</sup>Ra from <sup>229</sup>Th source material starts with removal of the <sup>229</sup>Th using solvent extraction or ion exchange from HNO<sub>3</sub>. DGA or DOODA resin can then be used to separate <sup>225</sup>Ac from <sup>225</sup>Ra and other <sup>229</sup>Th progeny and reagent impurities. Separation of <sup>225</sup>Ac from <sup>226</sup>Ra target material and <sup>226</sup>Ra progeny can also be achieved using DGA or DOODA resin. Separation of <sup>225</sup>Ac from <sup>232</sup>Th proton spallation targets also begins with removal of the bulk Th target, followed by purification of <sup>225</sup>Ac from <sup>225</sup>Ra and other spallation byproducts. Separation of <sup>225</sup>Ac from <sup>140</sup>La and other radio-lanthanide byproducts may also be necessary, and recovery of the <sup>225</sup>Ra is also important as a source of <sup>225</sup>Ac free of the long-lived <sup>227</sup>Ac spallation byproduct.

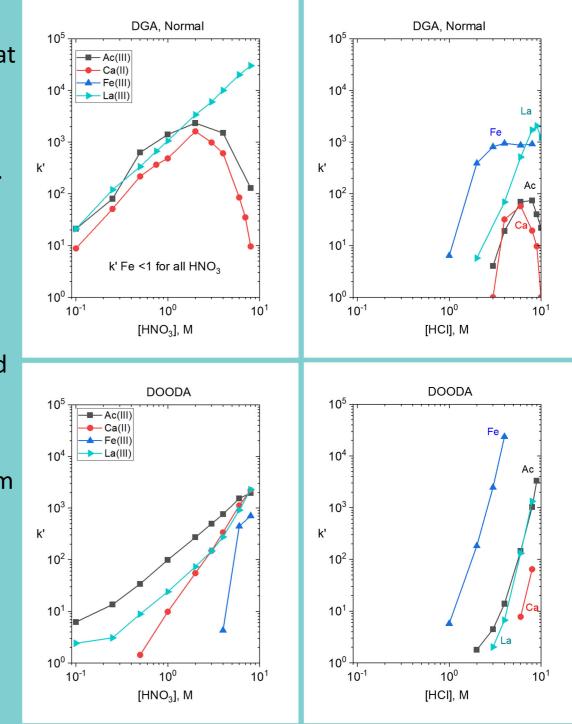
(2.16 m) <sup>209</sup>TI

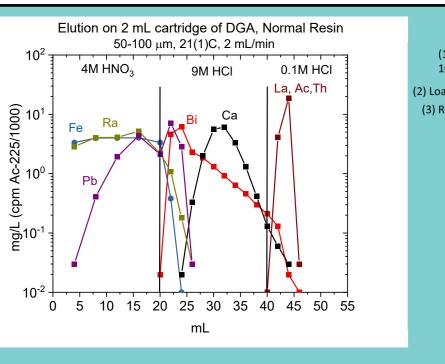


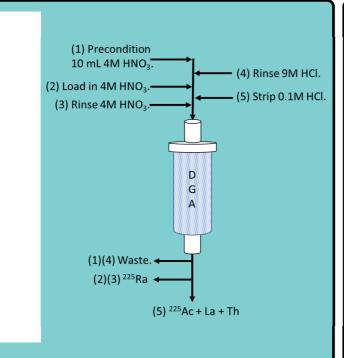


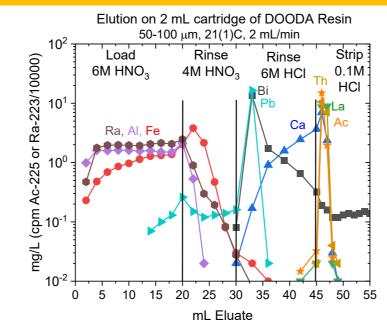
**Separation of Ac from Th/Ra/decay series** elements: DGA and DOODA resin both retain Ac strongly from HNO<sub>3</sub> and HCl. The Ac retention on DGA resin peaks at 2-3M HNO<sub>3</sub> and then decreases at higher HNO<sub>3</sub> concentrations. The retention of Ac on DOODA resin continues to increase even from 6-10M HNO<sub>3</sub>. Ra has essentially no retention on DGA resin from HNO<sub>3</sub> or HCl, but is slightly retained (k' 4-5) in 1-3M HNO<sub>3</sub> on DOODA resin. Po(IV) and Bi(III) will remain on the DGA and DOODA resin during standard elution conditions, while Pb will be rinsed away using an HCl rinse prior to recovery of Ac using dilute HCl. Additional Th decontamination can be achieved on DGA resin by recovering Ac in 2M HCl (Th remains on DGA). From DOODA resin, Ac can also be recovered using dilute HNO<sub>3</sub>.

Separtaion of Ac from La/reagent impurities: On DGA resin, La uptake continues to increase at high HNO<sub>3</sub> and HCl concentrations, while Ac retention decreases from 6-10M HNO<sub>3</sub>. This behavior can be utilized to separate Ac from La. On DOODA resin, La and Ac uptake both continue to increase at high HNO<sub>3</sub> and HCl concentrations. The differences in La and Ac behavior between DGA and DOODA enable unique separation opportunities when DGA and DOODA resin are used in tandem. Fe(III) impurities can impact the labeling of the final <sup>225</sup>Ac product. Fe(III) can easily be removed from Ac on DGA resin by rinsing with any HNO<sub>3</sub> concentration and on DOODA resin by rinsing with 3-4M HNO<sub>3</sub>. Many other common matrix impurities (Al, Na, K, Mg) are not retained by DGA or DOODA Resin. Ca can be removed with the appropriate HNO<sub>3</sub> or HCl rinse.

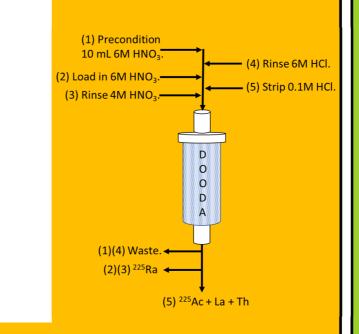




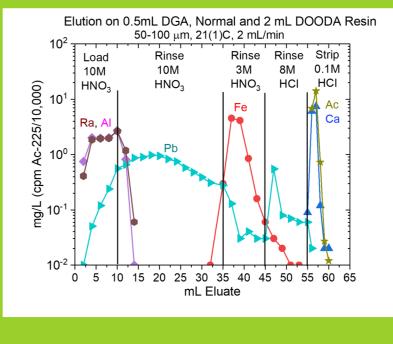


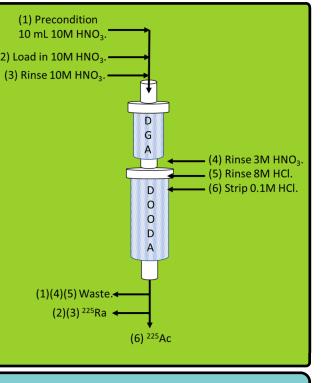


Relative Dw on DGA, Normal

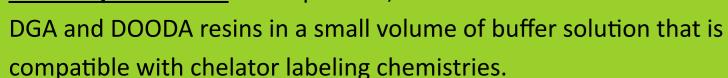


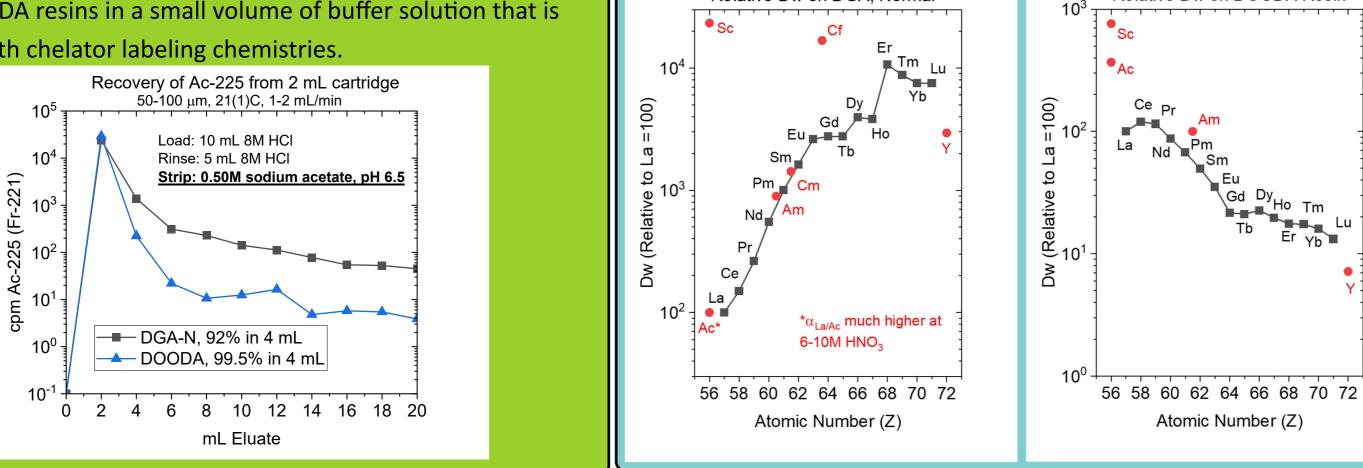
Relative Dw on DOODA Resin





**Recovery of Ac-225:** Once purified, <sup>225</sup>Ac can be recovered from the





**Future Work:** There are many differences between the DGA and DOODA resins. In particular, the selectivity for adjacent rare earth elements (REE) and trivalent actinides is very different for the DGA and DOODA resins. DGA resin extracts heavy REE more strongly, while DOODA extracts the light REE more strongly. This selectivity difference has been utilized for the separation of <sup>225</sup>Ac from rare earths and other impurities using a combination of the DGA and DOODA resins. Future work will contrast the selectivity of DGA and DOODA for other separations, including the preparation of <sup>44</sup>Sc, <sup>111</sup>In, <sup>90</sup>Y, <sup>89</sup>Zr and <sup>68</sup>Ga.

## **References:**

1) E. P. Horwitz, D. R. McAlister, A. H. Bond, R. E Barrans, Jr., "Novel Extraction Chromatographic Resins Based on Tetraalkyldiglycolamides: Characterization and Potential Applications," Solv. Extr. Ion Exch., 23, 319-344 (2005).

2) D.R. McAlister, E.P. Horwitz, "Selective Separation of Radium and Actinium from Bulk Thorium Target Material on Strong Acid Cation Exchange Resin from Sulfate Media," Applied Radiation and Isotopes, 140, 18-23 (2018).

3) M.A. Eddy, E. Rush, D. R. McAlister, "Novel Extraction Chromatographic Resins Based on the DOODA extractant: Characterization and Potential Applications," Solv. Extr. Ion Exch., submitted (2023).

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